

Characterization of Thermoset and Thermoplastic Polyurethane Pads, and Molded and Non-Optimized Machined Grooving Methods for Oxide CMP Applications

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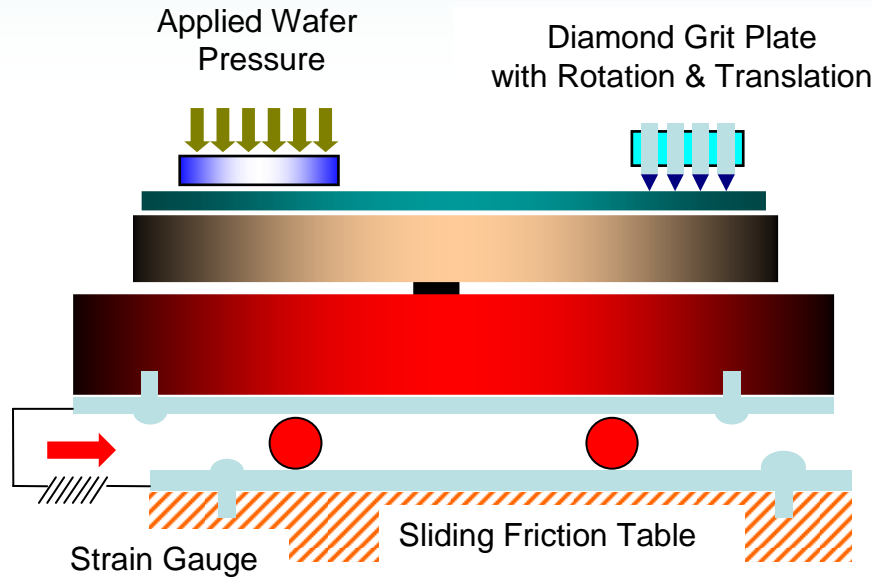
NEXPLANAR



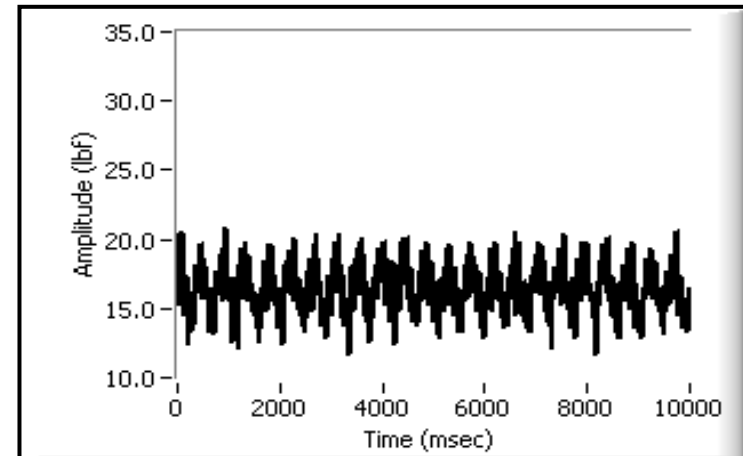
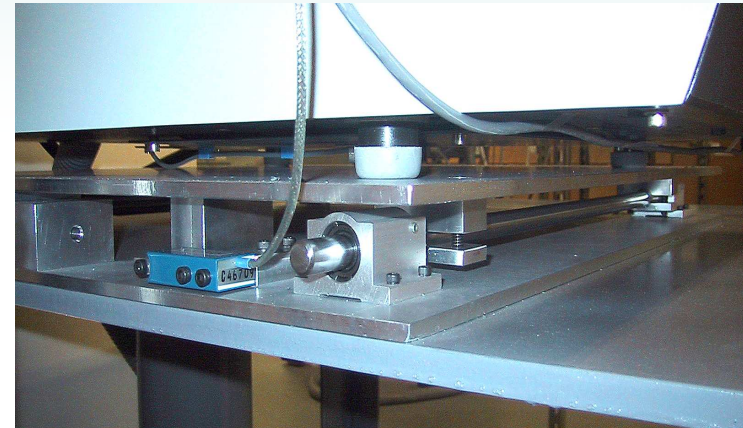
Objectives

- Investigate the effect of PU pad **synthesis methods** (i.e. thermoplastic and thermoset), **grooving methods** (i.e. molded and non-optimized machined grooving) and **groove types** (i.e. concentric and 'logarithmic – positive – spiral – positive') on:
 - Dynamic Mechanical Analyzer (DMA)
 - Coefficient of friction (COF)
 - Variance of shear force
 - Removal rate (RR)
 - Removal rate model
- Perform simulations using a two-step removal rate mechanism to estimate the chemical and mechanical rate constant

Polisher & Tribometer



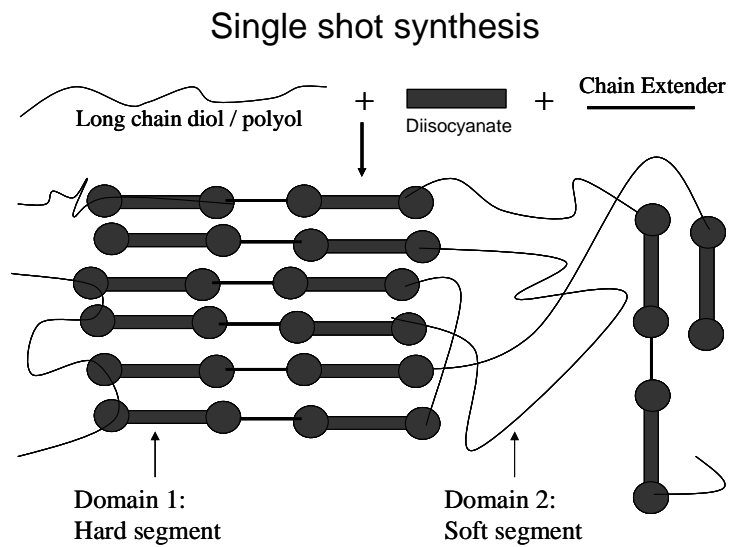
$$COF_{avg} = \frac{\bar{F}_{Shear}}{F_{Normal}}$$



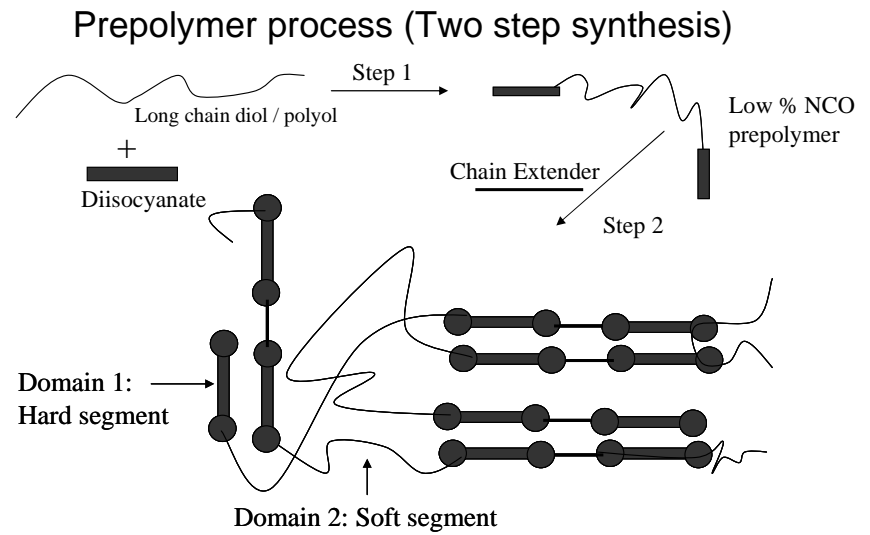
Experimental Conditions

- Diamond disc conditioner : TBW Industries 100 grit
- Conditioning pressure : 0.5 PSI
- Conditioning : *In-situ* at 30 RPM disc speed & 20 per minute sweep frequency
- Break-in time : 30 minutes
- Wafers : 100 mm blanket oxide
- Wafer pressure : 2, 3 and 4 PSI
- Sliding velocity : 0.32, 0.64, 0.96 and 1.24 m/s
- Slurry : Fujimi PL-4217
- Slurry flow rate : 80 cc/min
- Pad :
 - Thermoplastic non-optimized machined concentric groove
 - Thermoplastic molded concentric groove
 - Thermoset non-optimized machined concentric groove
 - Thermoset non-optimized machined logarithmic spiral positive groove
- Polishing time: 60 seconds

Thermoplastic and Thermoset Synthesis

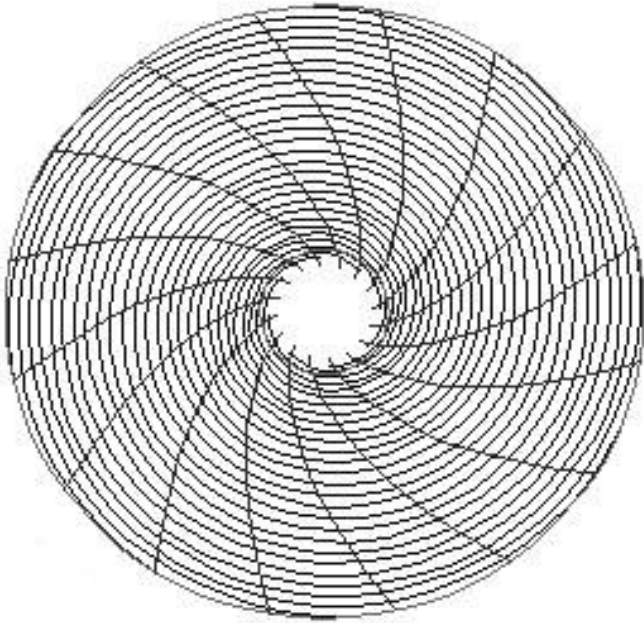


Thermoplastic



Thermoset

Pad Grooving Types

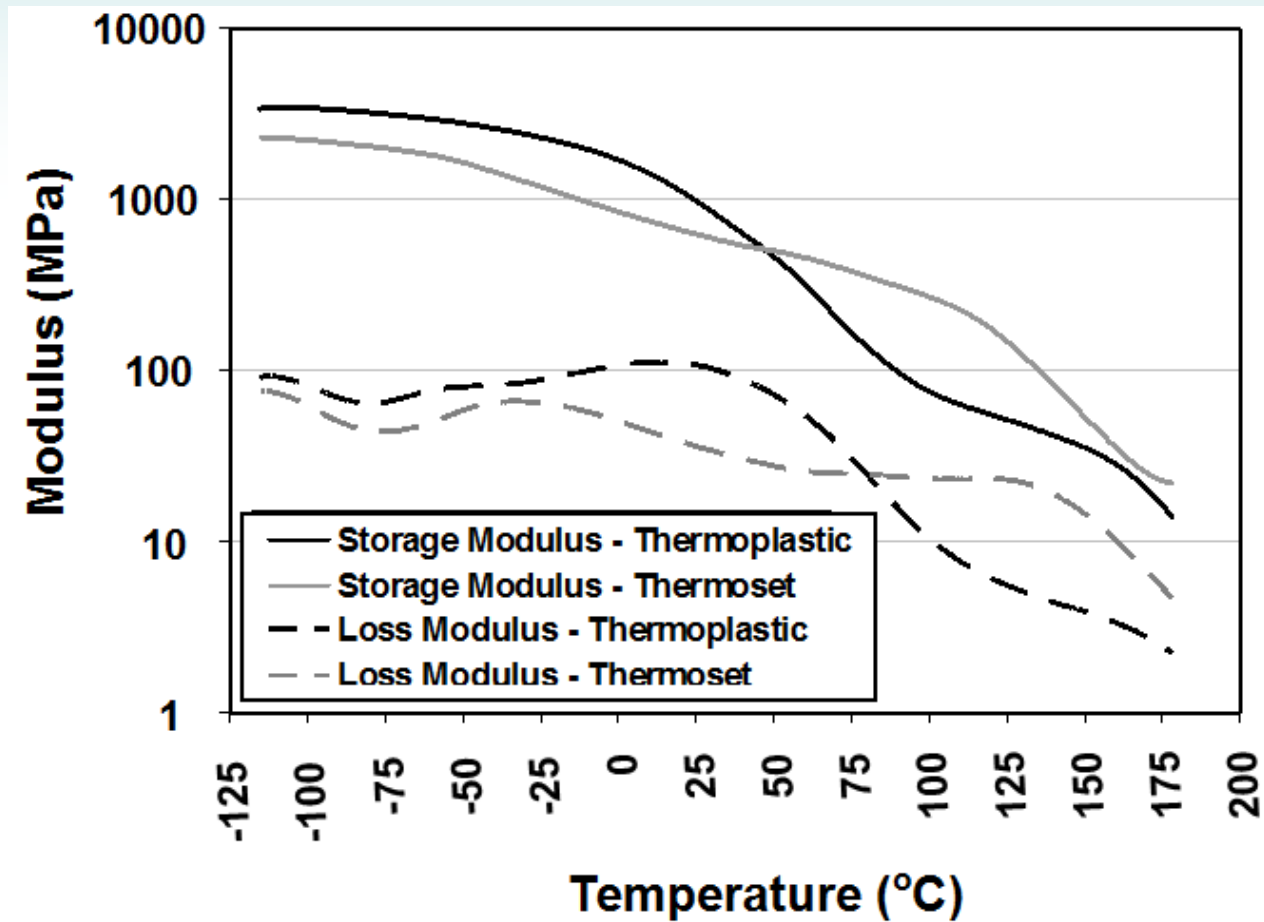


Logarithmic Positive Spiral Positive
(LPSP)



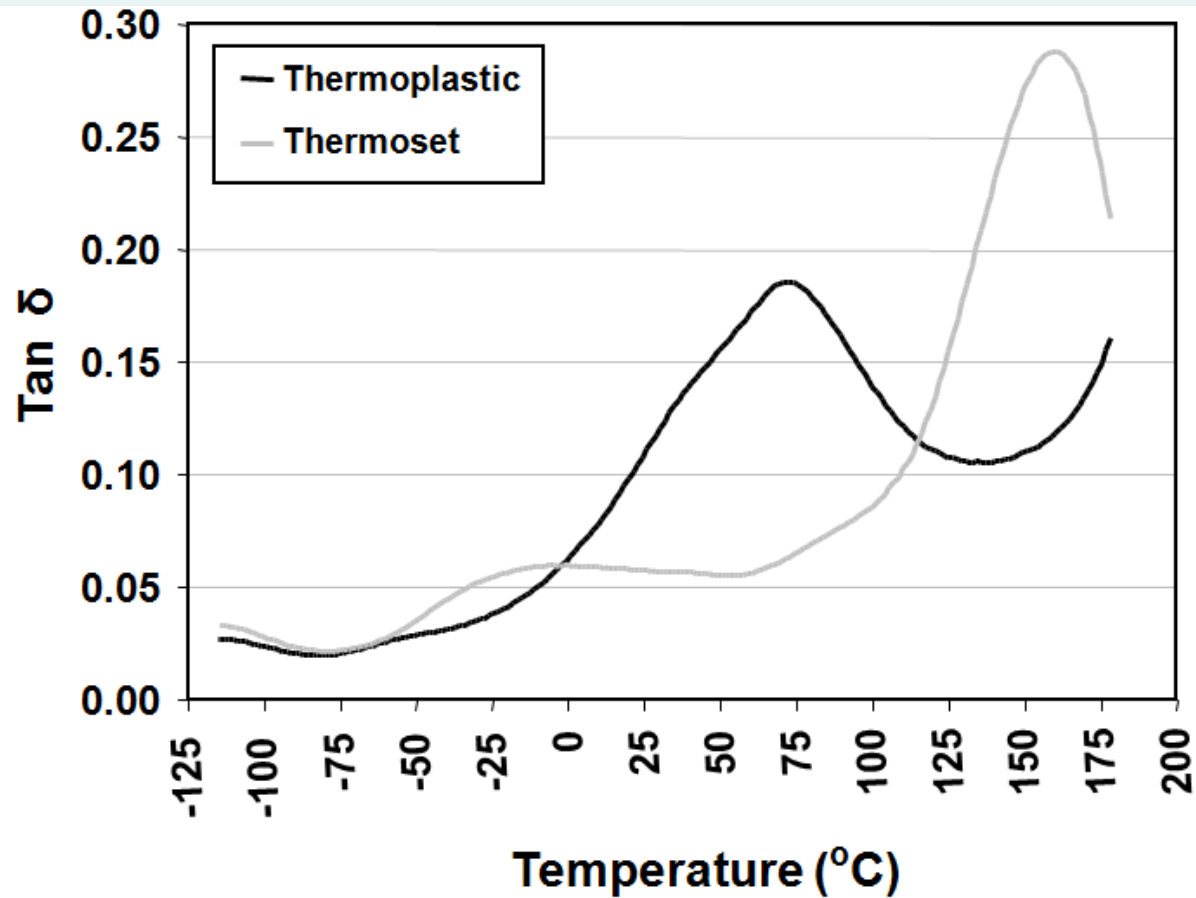
Concentric

DMA Results



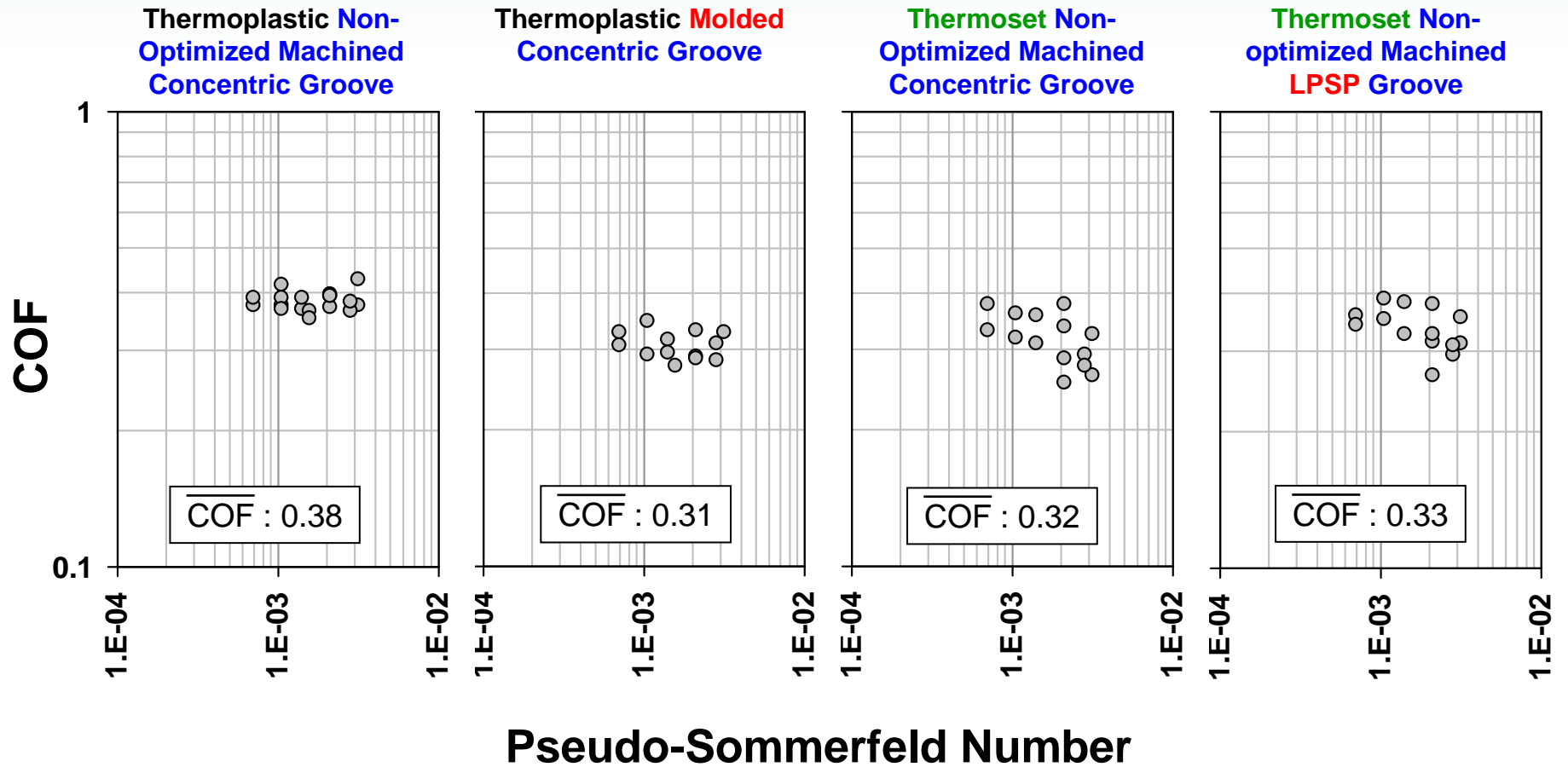
Lightly cross-linked polymers have a steeper modulus slope than more heavily cross-linked polymer. (Rodriguez, "Principles of Polymer Systems", 1996)

DMA Results (cont...)

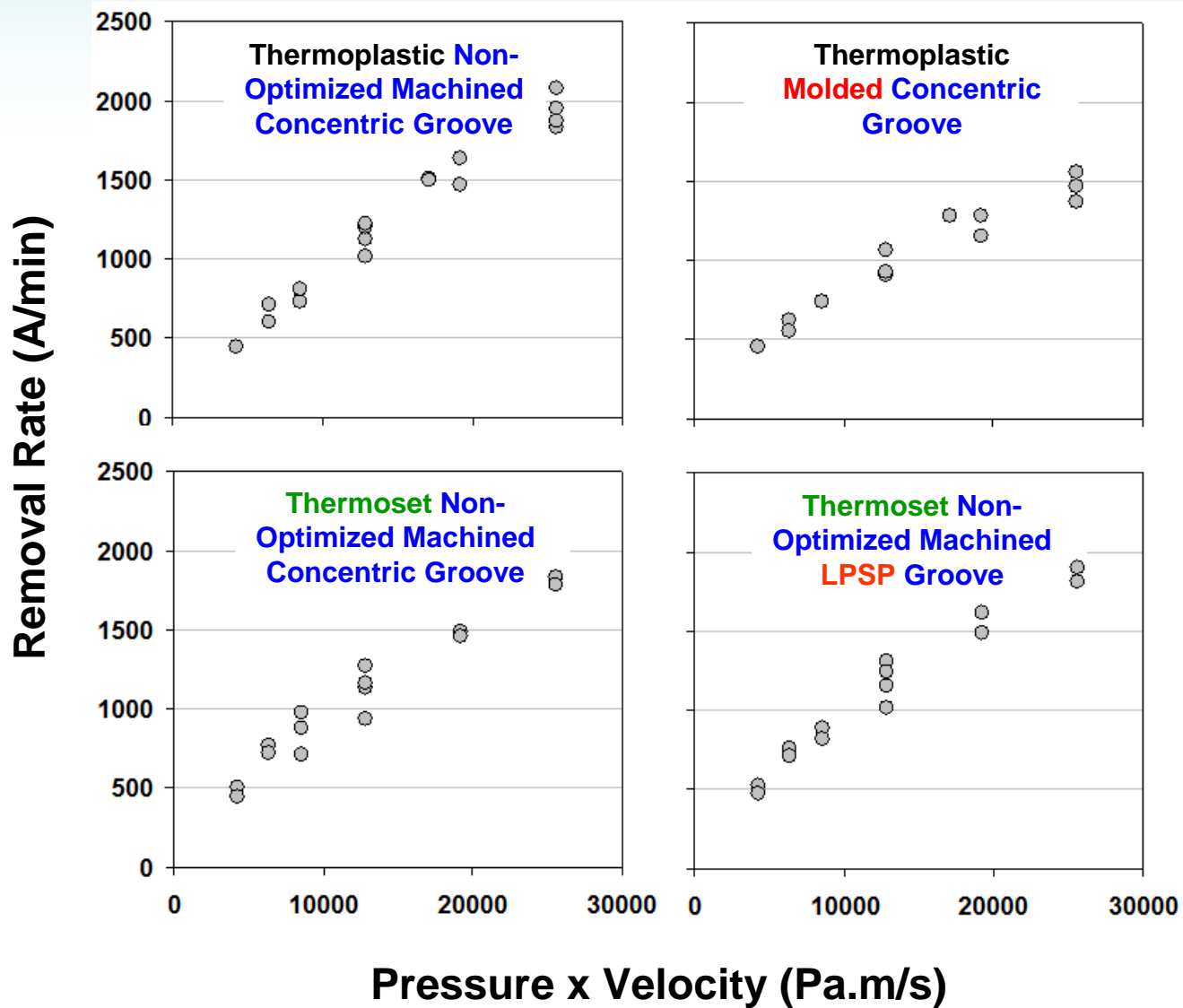


The total energy loss during a stick-slip event is proportional to the damping factor ($\tan \delta$) of the material and that this energy must be equated to the external work of friction. (Moore, "Principles and Applications of Tribology", 1975 and Bartenev & Lavrentev, "Friction and Wear of Polymers", 1981)

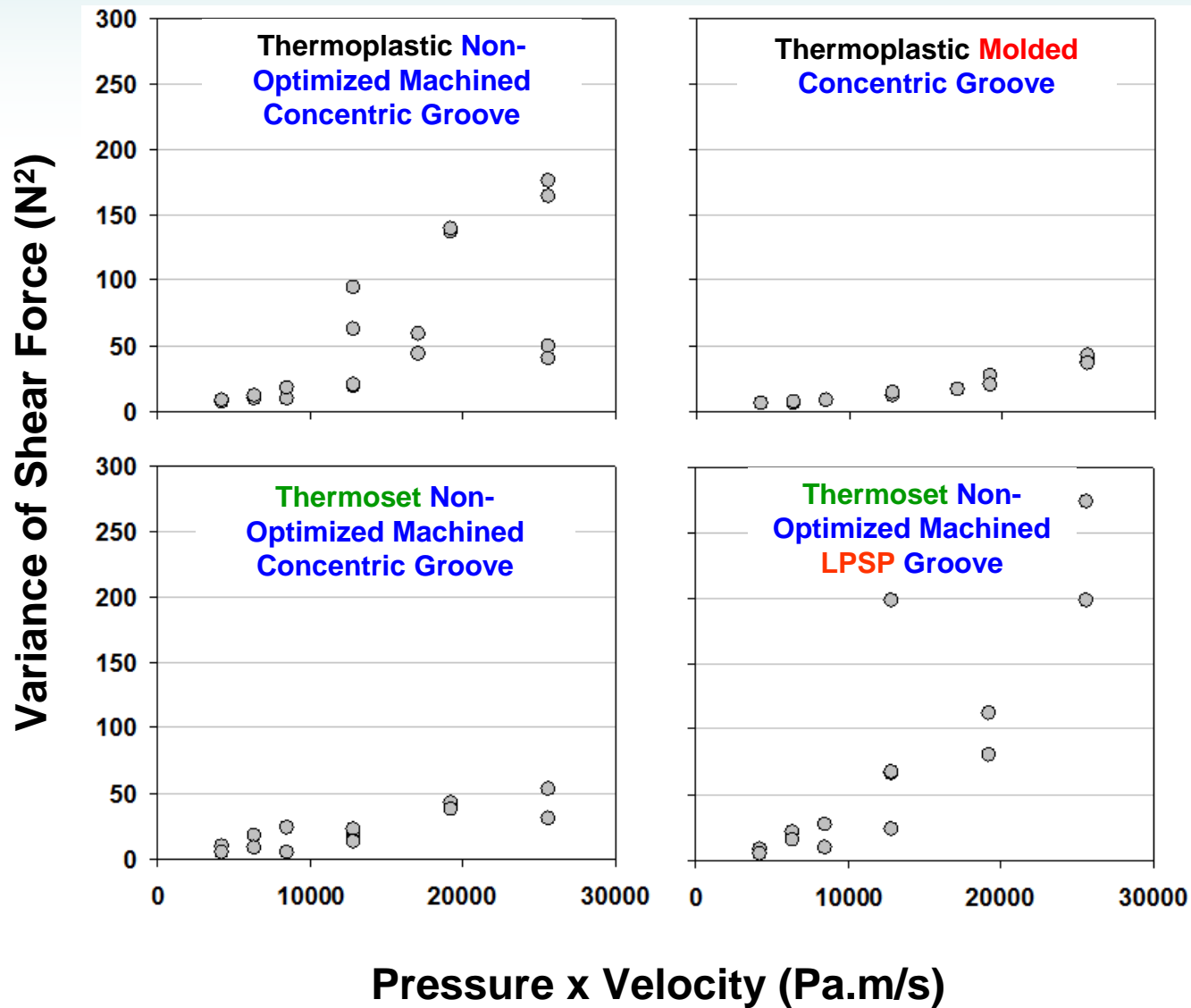
Stribeck Curves



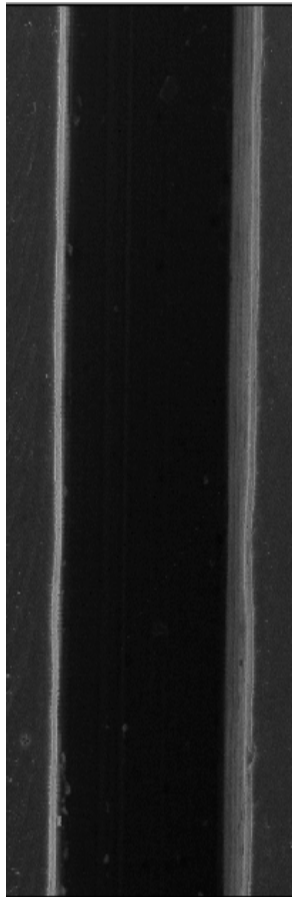
Removal Rate



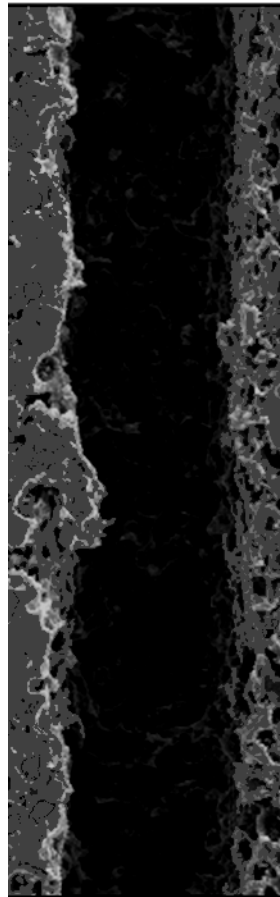
Variance of Shear Force



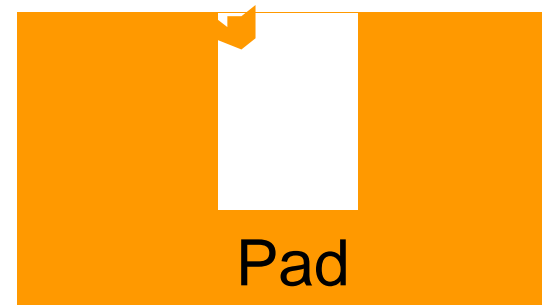
SEM Images and Conceptualization of Burrs



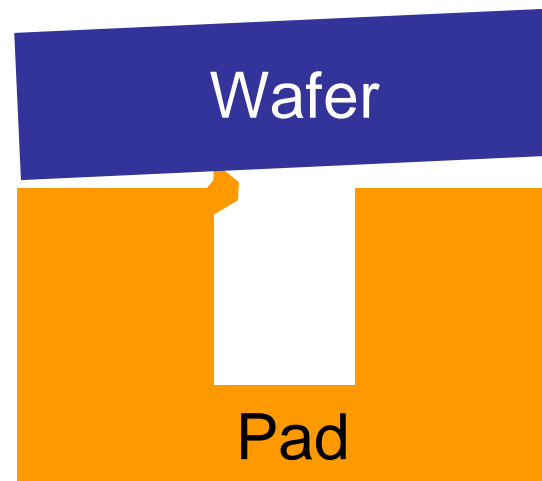
**Molded
Groove**



**Non-Optimized
Machined Groove**



Pad

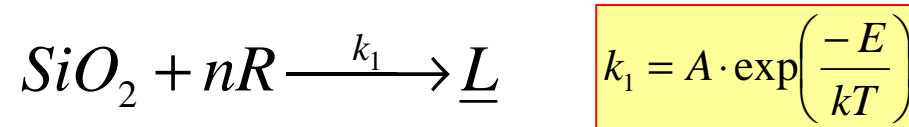


Wafer

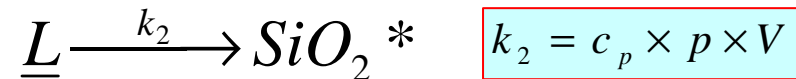
Pad

Removal Rate Model

- Oxide removal in the Langmuir-Hinshelwood model:
 - n moles of reactant R in the slurry react at rate k_1 with oxide film on the wafer to form a product layer \underline{L} on the surface



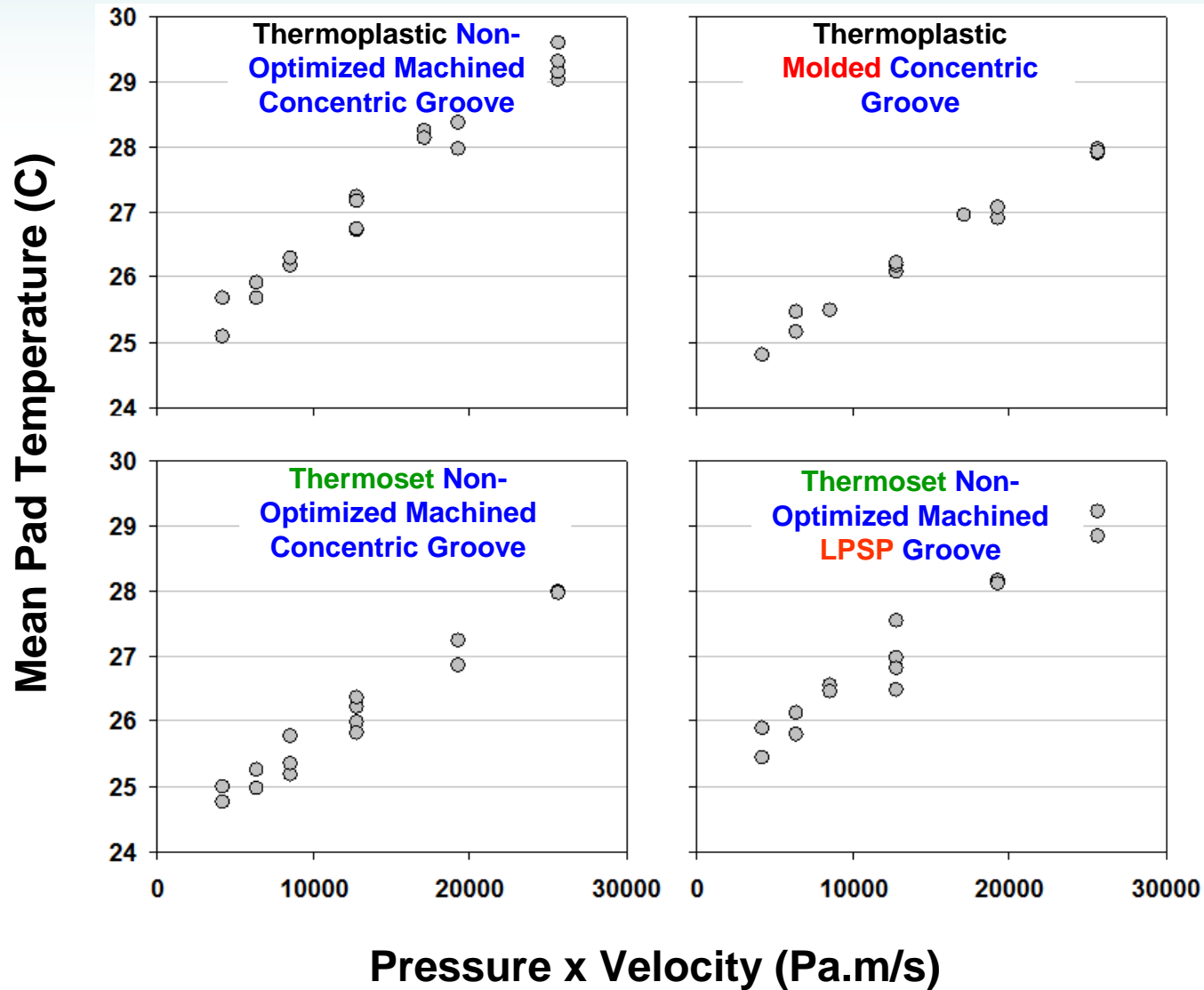
- Product layer \underline{L} subsequently removed by mechanical abrasion with rate k_2



- Abraded material L is carried away by the slurry
- The local removal rate in this mechanism therefore is a function of chemical and mechanical contributions

$$RR = \frac{M_w}{\rho} \frac{k_2 k_1}{k_2 + k_1}$$

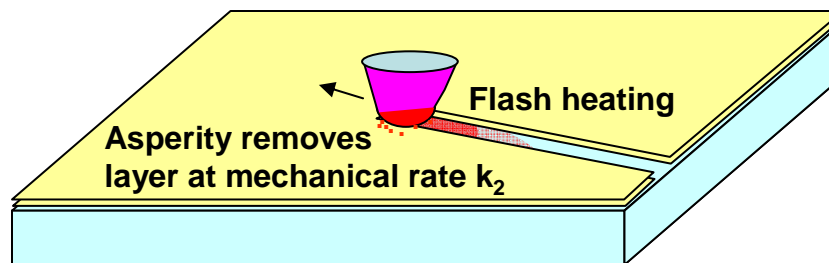
Pad Temperature



Physical Temperature Model

$$\bar{T} = T_p + \frac{2\zeta}{\sqrt{\pi\kappa\rho C_p}} \frac{\gamma_p (p_a/p)}{V^{1/2}} \mu_k p V$$

Geometric factor: 2ζ
 Fraction of heat conducted to pad: γ_p
 Depends on contact area: (p_a/p)
 Pad thermal properties: $\sqrt{\pi\kappa\rho C_p}$
 Mean asperity tip contact pressure: $V^{1/2}$
 COF: μ_k



Surface layer grows at chemical rate k_1 .
 Growth is fastest at the flash temperature

(Borucki, CPMIC 2005)

Flash Heating Temperature

- $T \equiv$ hydrolyzed layer reaction temperature
- Reaction temperature is due to flash heating by passing slurry particle-laden asperity tips

$$T = T_p + \zeta \frac{\gamma_p \mu_k}{\sqrt{\kappa \rho C_p}} \left[\frac{(p_a / p)}{V^{1/2}} \right] pV$$

- The quantity in brackets depends on V due to fluid dynamic effects. Assuming a power law dependence:

$$T = T_p + \frac{\beta}{V^{1/2+e}} \mu_k pV$$

- The model has five fitting parameters: A , E , c_p , β & e :

$$RR = \frac{M_w}{\rho} \frac{(c_p \cdot pV) \cdot Ae^{\left(\frac{-E}{k \left(T_p + \frac{\beta}{V^{1/2+e}} \mu_k pV \right)} \right)}}{(c_p \cdot pV) + Ae^{\left(\frac{-E}{k \left(T_p + \frac{\beta}{V^{1/2+e}} \mu_k pV \right)} \right)}}$$

Optimized Fitting Parameters

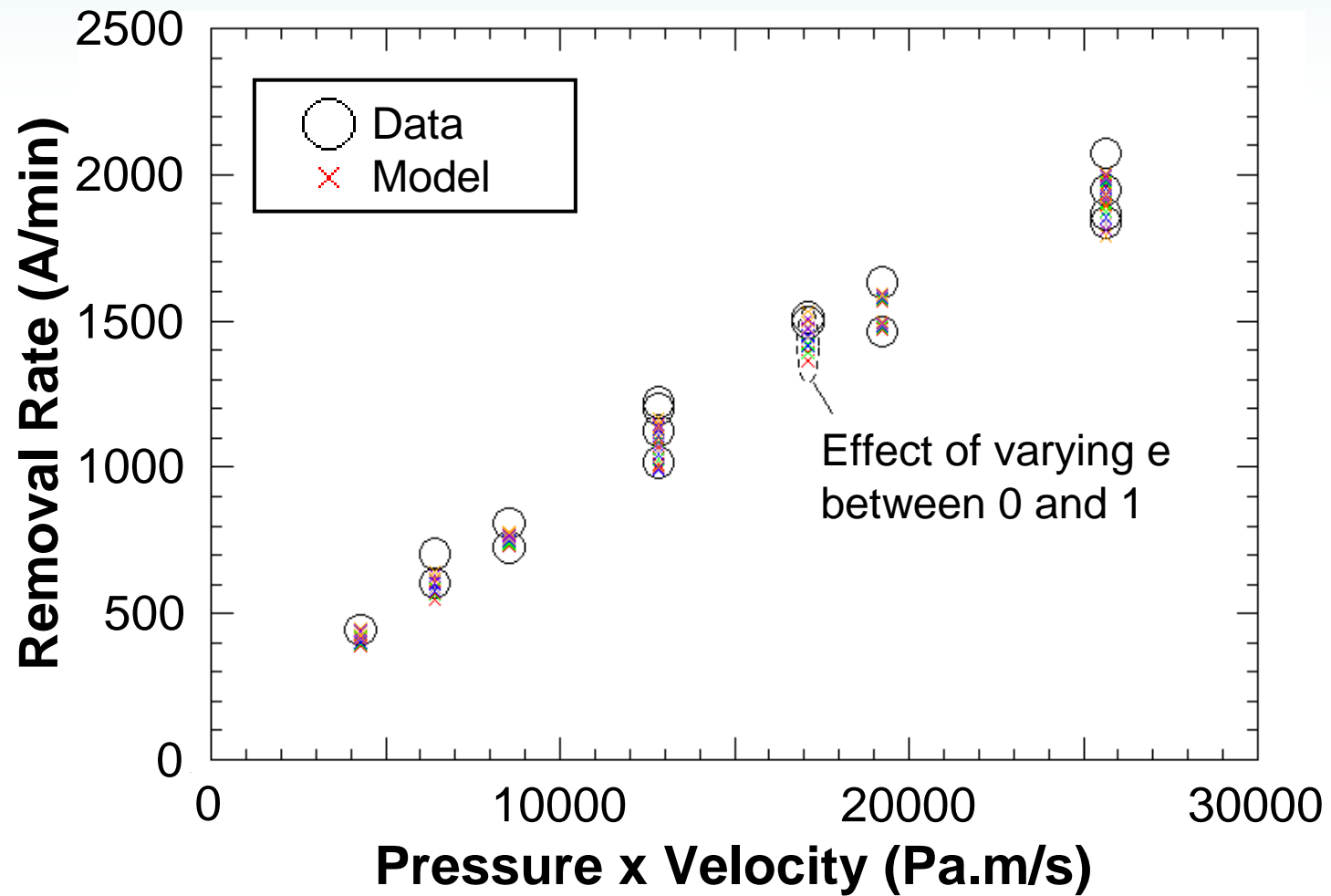
Polishing pad	C_p (moles/J)	β (K/Pa-(m/s) ^{1-a})	RMS Error (Å/min)
Thermoplastic machined concentric groove	1.64E-8	2.15E-3	77
Thermoplastic molded concentric groove	1.74E-8	2.15E-3	78
Thermoset machined concentric groove	2.59E-8	1.45E-3	81
Thermoset machined LSP	2.52E-8	1.45E-3	65

$E = 0.53$ eV *from Sorooshian et al., Journal of Tribology, 127, 639 (2005)*

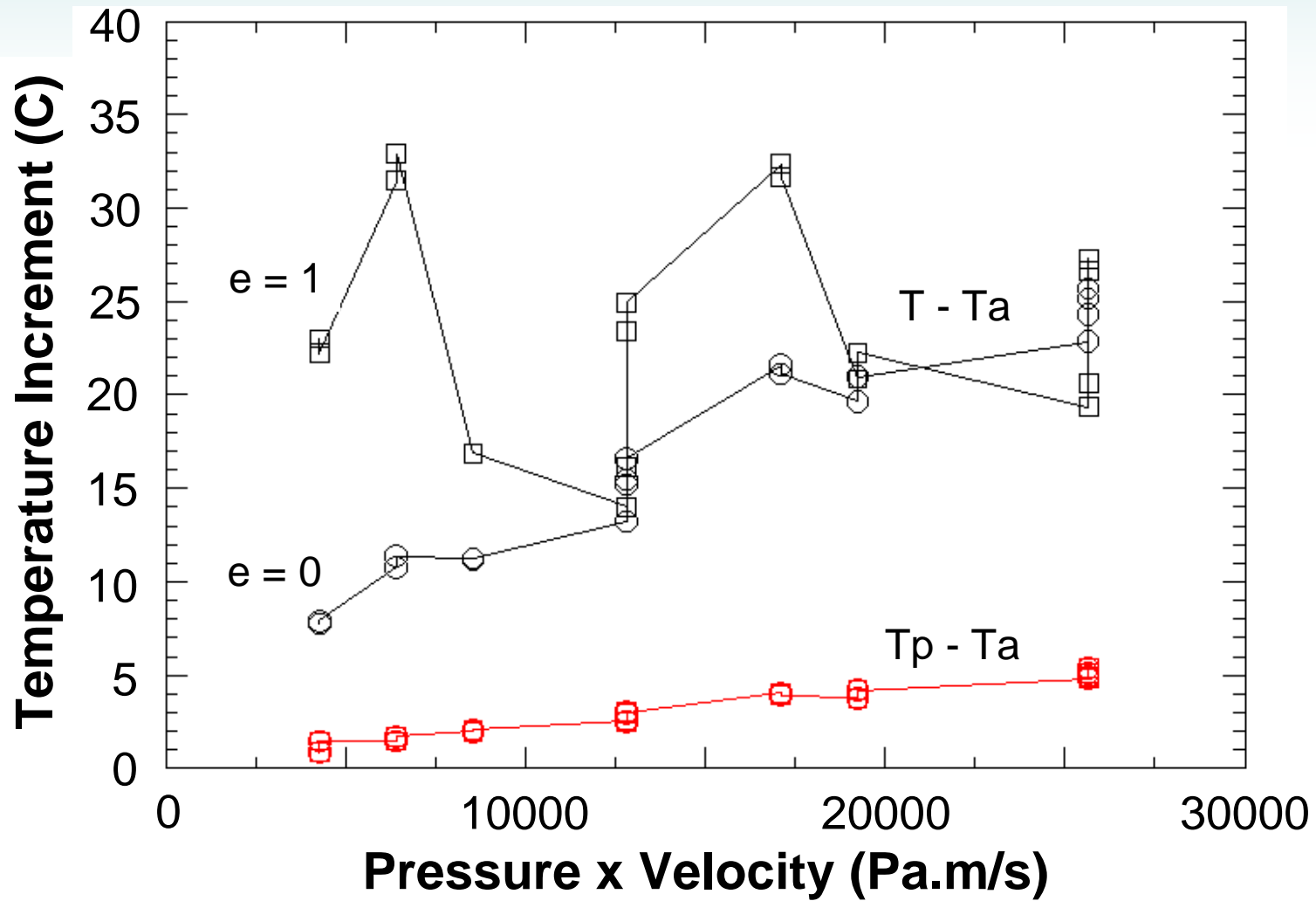
$e = 0.66$

$A = 1.02 \times 10^5$ moles $m^{-2} s^{-1}$

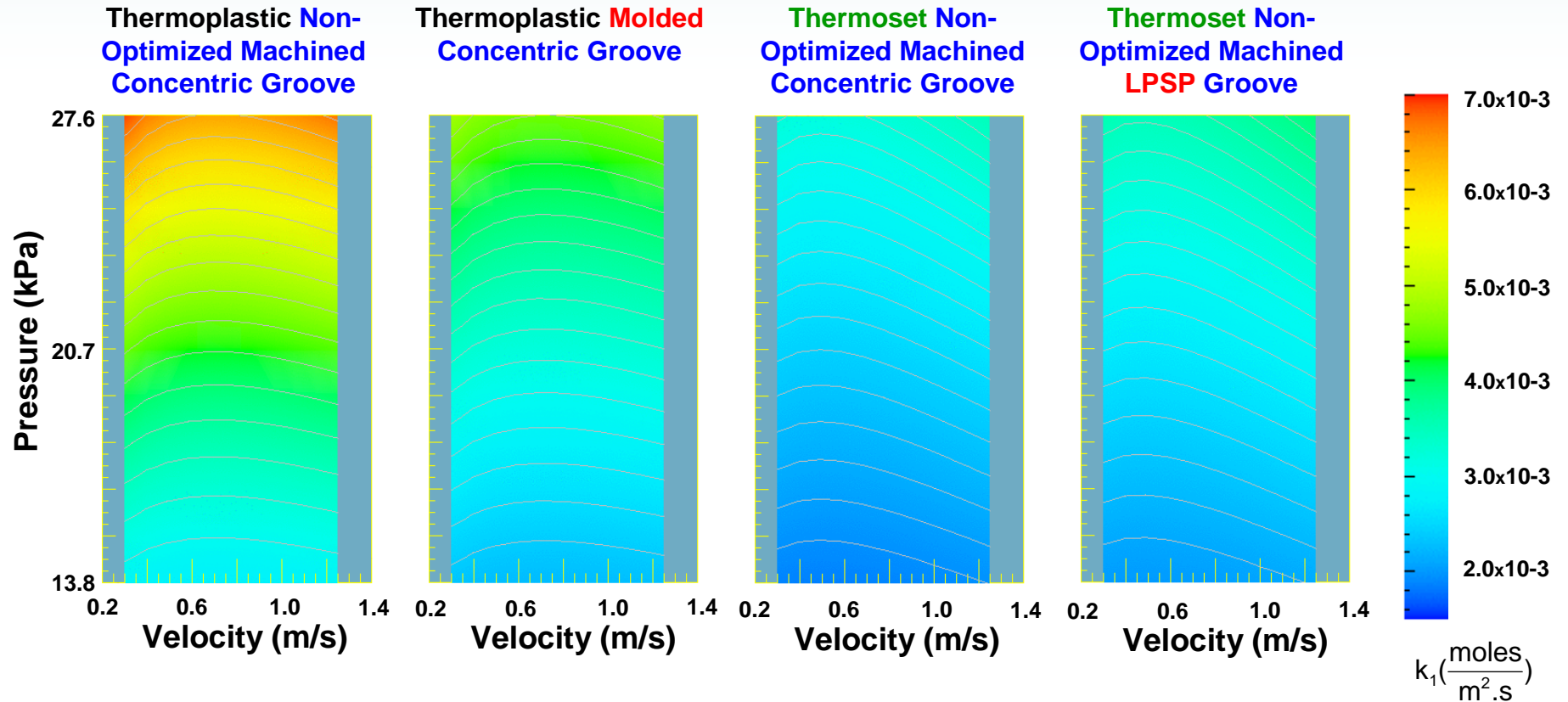
Sensitivity of 'e'



Contribution of Flash Heating Temperature

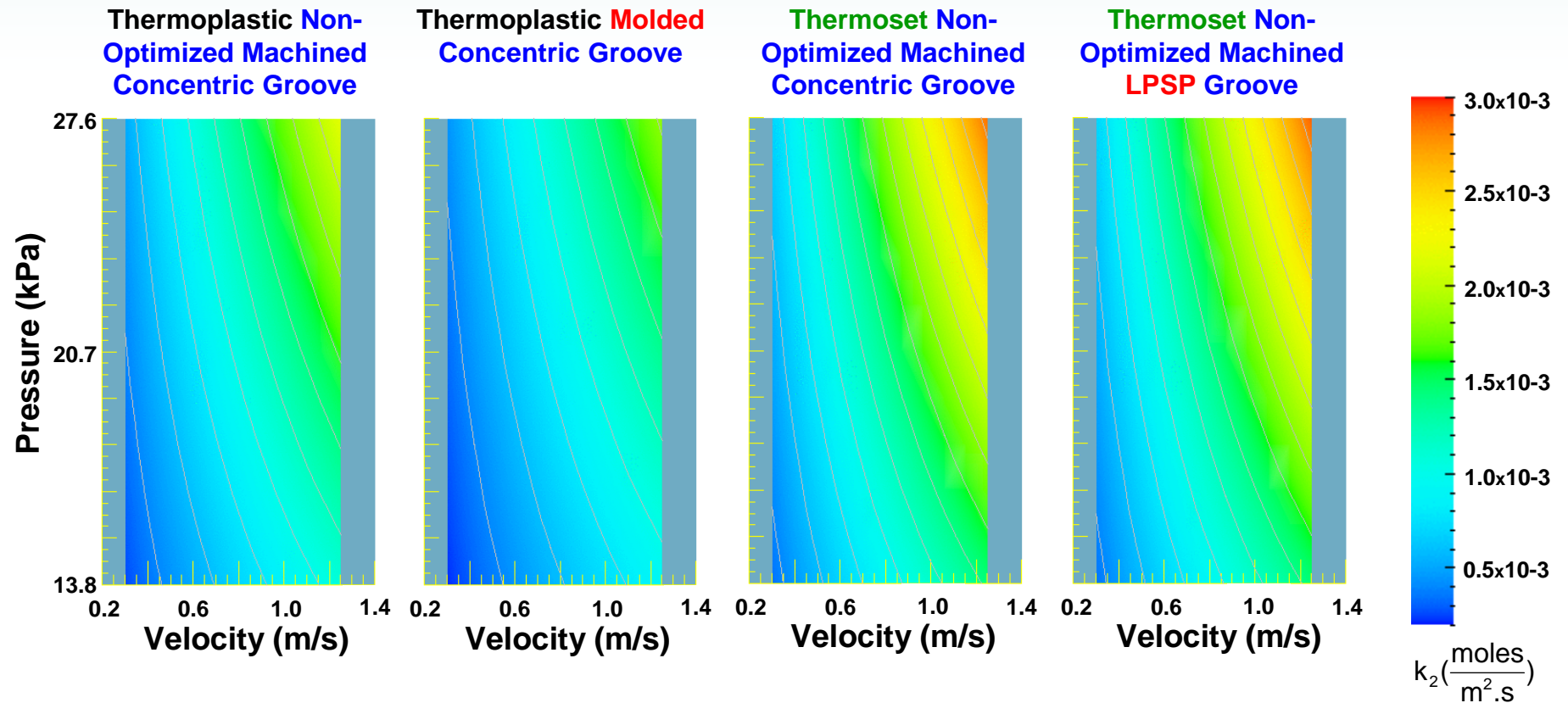


Chemical Reaction Rate Constant, k_1



Thermoplastic pads exhibit higher chemical reaction rate constant than thermoset pads

Mechanical Abrasion Rate Constant, k_2



Thermoplastic pads exhibit lower mechanical abrasion rate constant than thermoset pads

Summary

- **Thermoplastic pads induce higher COFs than the thermoset pads due to their inherently higher degree of energy loss.**
- **Since thermoplastic pads exhibit more reduction in storage modulus, the variance of shear force associated with thermoplastic pads is higher than thermoset pads.**
- **Un-optimized machined grooves produce rougher edges than molded grooves, thereby inducing a higher COF and a higher shear force variance.**
- **LPSP groove is designed to bring slurry towards the pad center, resulting in a higher mean pad temperature. In addition, the LPSP pad induces a higher shear force variance.**
- **Simulation results indicate that thermoplastic pads produce a more mechanically controlled removal than thermoset pads.**